

## EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	223322	(semiconductor or wafer or substrate) near10 (clean\$3 or wash\$3 or rins\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2011/06/29 15:40
L2	810	I1 and (nozzle or port) near8 \$3atomiz\$4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2011/06/29 15:41
L3	429	I2 and gas near8 liquid	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2011/06/29 15:42
L4	2	I3 and (step or ramp) near5 (port or passage)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2011/06/29 15:42
L5	68	I2 and mix\$3 near5 gas near5 liquid	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2011/06/29 15:44
L6	3490	(134/94.1,95.1,95.2,95.3,144,157).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2011/06/29 15:46
L7	915	I6 and (semiconductor or wafer or substrate) near10 (clean\$3 or wash\$3 or rins\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2011/06/29 15:46

## EAST Search History (Prior Art)

L8	53	17 and (nozzle or port) mix\$3 near5 gas near5 liquid	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2011/06/29 15:46
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